

IN THE CLAIMS AMEND

1. (Deleted)
2. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in claim ~~15~~⁴, wherein a throttle valve (23) is disposed in at least one supply line (21) for the gas directing device (11).
3. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in claim ~~15~~⁴, wherein the gas directing device is formed by at least one nozzle (11), which is connected by the supply line (21) to a gas source (22).
4. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in claim ~~15~~⁴, wherein a plurality of gas directing devices (11) are provided, with each of which a throttle valve (20) in a supply line section (19) is associated.
5. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in claim ~~15~~⁴, wherein an adjustable holding device (9) for the gas directing device (11) is provided.
6. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in claim 5, wherein the holding device (9) comprises an adjusting device (12) for adjusting the axial position of the gas directing device (11) relative to the optical element (5).
7. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in claim 5, wherein the holding device (9) comprises an adjusting device (12) for adjusting the inclination of the gas directing device (11) relative to the optical element (5).
8. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in claim 2, wherein there is a control device (25) with a communication link to the at least one throttle valve (20, 23) for selecting a volumetric flow of gas in the gas directing device (11).

9. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in claim 8, wherein the control device (25) has a communication link (27, 28, A) to the light source (2) for receiving a signal corresponding to the light output of the light source, wherein the selection of the volumetric flow of a gas is effected by the control device (25) in dependence upon the transmitted signal of the light source (2).

10. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in claim 8, wherein there is a sensor arrangement (31) with a communication link (27, 28, 30) to the control device (25) for monitoring the imaging quality of the optical element (5) and/or of the optical arrangement (4, 5), wherein the selection of the volumetric flow of gas is effected by the control device (25) in dependence upon the transmitted signal data of the sensor arrangement (31).

11. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in claim 10, wherein the sensor arrangement comprises a CCD array (31).

12. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in claim 15, wherein the gas directing device (11) is part of a sweeping device for the optical element (5).

13. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in claim 15, wherein there is a thermostatted tempering device (24) in the supply line (21).

14. (Currently Amended) ~~An optical arrangement~~ A projection printing installation as claimed in ~~one of the preceding claims~~ claim 15, wherein the gas directing device (11) is part of a sweeping device for the ~~optical arrangement~~ projection printing installation (4, 5).

15. (New) A microlithographic projection printing installation having a rotationally non-

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symmetrical illumination and comprising a light source which emits radiation, an optical element which is heated by the radiation, and a supply apparatus for gas tempering the optical element, wherein the supply apparatus comprises at least one gas supply line and at least one gas directing device for directing a gas flow onto the optical element, the gas directing device being adjustable so as to change the area of the optical element that is exposed to the gas flow.
